

What is claimed is:

1. An apparatus for processing a substrate, comprising:  
a substrate holder for holding and rotating a  
5 substrate;  
a scattering prevention cup for circumferentially  
surrounding the substrate held by the substrate holder to  
prevent a substrate processing liquid supplied to the  
substrate from being scattered around; and  
10 a scattering prevention cup cleaner for cleaning an  
inner wall surface of the scattering prevention cup.
2. An apparatus according to claim 1, wherein the  
scattering prevention cup is vertically movable between a  
15 lower substrate transfer position, an upper scattering  
prevention position, and a cleaning position between the  
lower substrate transfer position and the upper scattering  
prevention position.
- 20 3. An apparatus according to claim 1, wherein the  
scattering prevention cup cleaner is arranged to clean the  
inner wall surface of the scattering prevention cup with a  
cleaning liquid supplied to the substrate.
- 25 4. An apparatus for processing a substrate, comprising:  
a substrate holder for holding and rotating a  
substrate; and

a substrate holder cleaner for cleaning the substrate holder.

5. An apparatus according to claim 4, wherein the  
5 substrate holder cleaner comprises a plurality of cleaning liquid supply nozzles.

6. An apparatus according to claim 5, further  
10 comprising;

a scattering prevention cup for circumferentially surrounding the substrate held by said substrate holder to prevent a substrate processing liquid supplied to the substrate from being scattered around;

15 wherein at least one of the cleaning liquid supply nozzles being mounted on the scattering prevention cup.

7. An apparatus for processing a substrate, comprising:  
a substrate holder for holding and rotating a  
20 substrate;

a processing liquid supply portion for supplying a substrate processing liquid to the substrate held by said substrate holder; and

a processing liquid supply portion cleaner for cleaning  
25 the processing liquid supply portion.

8. A method of processing a substrate, comprising:  
processing a substrate with a chemical liquid;

cleaning at least one of a substrate holder for holding  
and rotating the substrate, an inner wall surface of a  
scattering prevention cup for circumferentially surrounding  
the substrate held by the substrate holder to prevent a  
5 substrate processing liquid supplied to the substrate from  
being scattered around, and a processing liquid supply  
portion for supplying a substrate processing liquid to the  
substrate held by the substrate holder; and then

cleaning the substrate which has been processed by the  
10 chemical liquid.